

	Hits	Search Text	DBs
22	0	((half near4 tone) same attenuat\$4 same (partial\$4 near9 transmit\$4 near12 phase near12 shift\$4) same ("180" or (hundred near5 eighty)) same degree same (mask or reticle or photomask)) and ((mask or photomask or reticle) same (partial\$\$ near16 transmit\$4 near16 (phase near6 shift\$4)) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((dual near9 layer) or (double near9 layer) or (upper near16 layer near16 lower)) same (resist or photoresist or photosensitive))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
23	0	((mask or photomask or reticle) same (partial\$\$ near16 transmit\$4 near16 (phase near6 shift\$4)) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((dual near9 layer) or (double near9 layer) or (upper near16 layer near16 lower)) same (resist or photoresist or photosensitive))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
24	0	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4 or light) same (partial\$4 near9 transmit\$4) same (block\$4 or shiled\$4) same (fully near9 transmit\$4) same ("180"))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	0	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((dual near9 layer) or (double near9 layer) or (upper near16 layer near16 lower)) same (resist or photoresist or photosensitive)) and ((partial near9 transmit\$4) same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
26	3	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((dual near9 layer) or (double near9 layer) or (upper near16 layer near16 lower)) same (resist or photoresist or photosensitive)) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	9	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((dual near9 layer) or (double near9 layer) or ((upper or top) near29 (bottom or lower))) same (resist or photoresist or photosensitive)) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	2	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top) near29 (bottom or lower)))) near39 (resist or photoresist or photosensitive) near29 (substrate or wafer))) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
29	12	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top) near29 (bottom or lower)) or (first near22 second)) near26 (resist or photoresist or photosensitive) near29 (substrate or wafer))) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	4	((mask or photomask or reticle) same ((phase near6 shift\$4) or (half near9 tone)) same (expos\$4 or irradiat\$4 or illuminat\$4) same (partial\$4 near9 transmit\$4) same ((resist or photoresist or photosensitive) near9 (two or dual or double or (top near9 bottom) or (upper near9 bottom)) near9 (layer or film or coat\$4)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	11	((mask or photomask or reticle) same ((phase near6 shift\$4) or (half near9 tone)) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top) near12 (bottom or lower)) or (first near12 second)) near6 (resist or photoresist or photosensitive) near9 (substrate or wafer))) and (partial\$4 near9 transmit\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	0	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same (partial\$4 near9 transmit\$4) same (block\$4 or shiled\$4) same (fully near9 transmit\$4) same ("180"))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
33	0	((half near4 tone) same attenuat\$4 same (partial\$4 near9 transmit\$4 near12 phase near12 shift\$4) same ("180" or (hundred near5 eighty)) same degree same (mask or reticle or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
34	2	((mask or photomask or reticle) same ((alternat\$4 near12 phase near9 shift\$4) or (phase near6 shift\$4) or (half near9 tone)) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top or first) near22 (bottom or lower or second)) or (first near12 second)) near20 (resist or photoresist or photosensitive) near9 (substrate or wafer))) and (partial\$4 near9 transmit\$4) and (dual near9 damascene)	US-PGPUB
35	6	((mask or photomask or reticle) same ((alternat\$4 near12 phase near9 shift\$4) or (phase near6 shift\$4) or (half near9 tone)) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top or first) near22 (bottom or lower or second)) or (first near12 second)) near20 (resist or photoresist or photosensitive) near9 (substrate or wafer))) and (partial\$4 near9 transmit\$4) and (dual near9 damascene)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB